

# Analog performance of the Screen Grid Field Effect Transistor

EPSRC

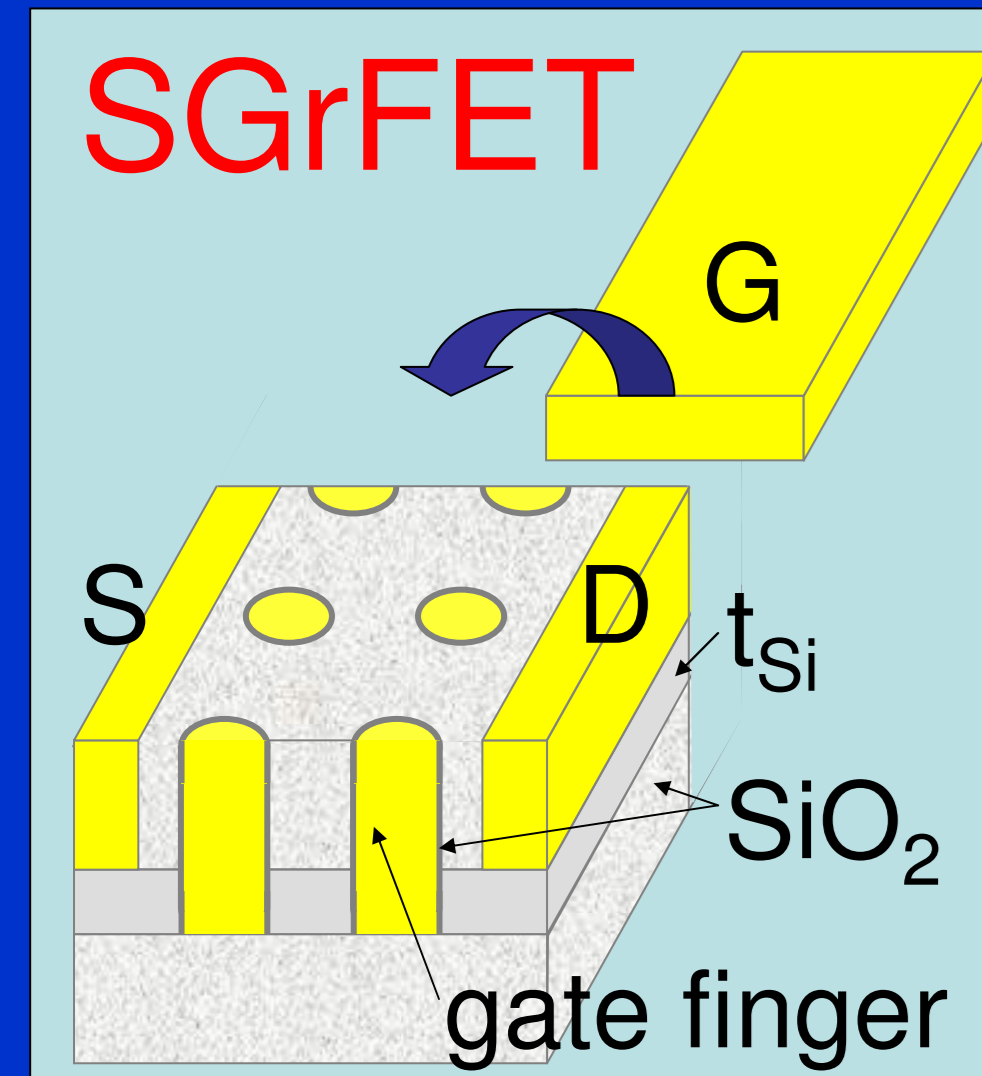
Imperial College  
London

P.W. Ding, K. Fobelets, and J.E. Velazquez-Perez

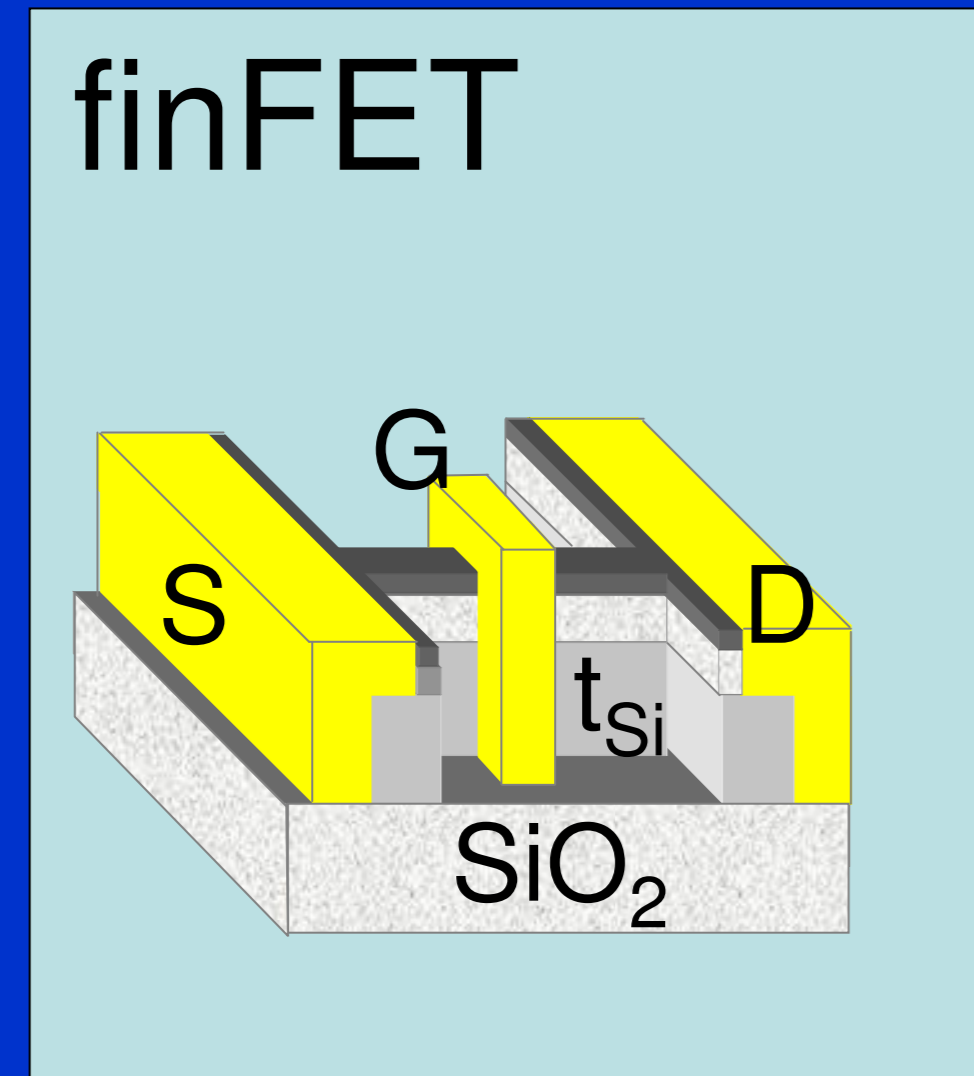
University  
of  
Salamanca

## Novel gating geometry/

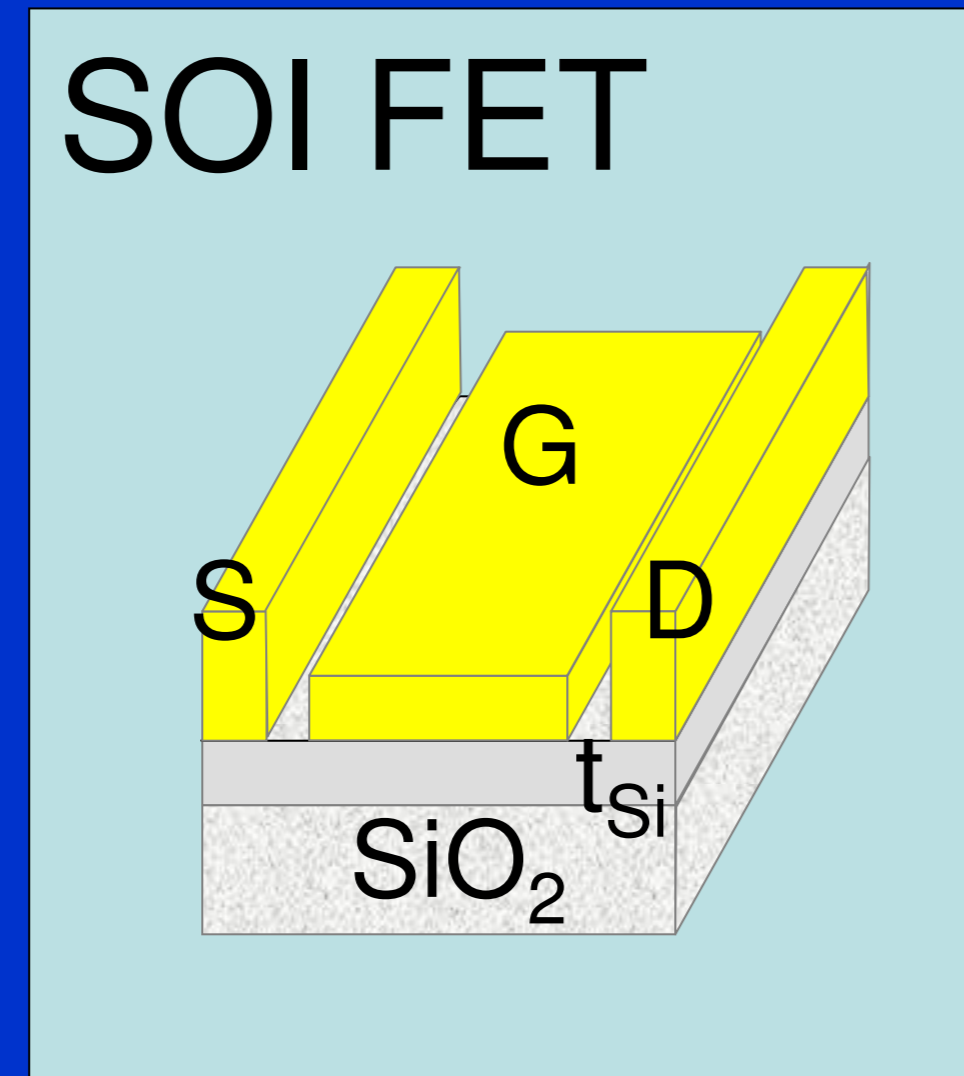
### 3D view



In-plane transport  
Large SD contact



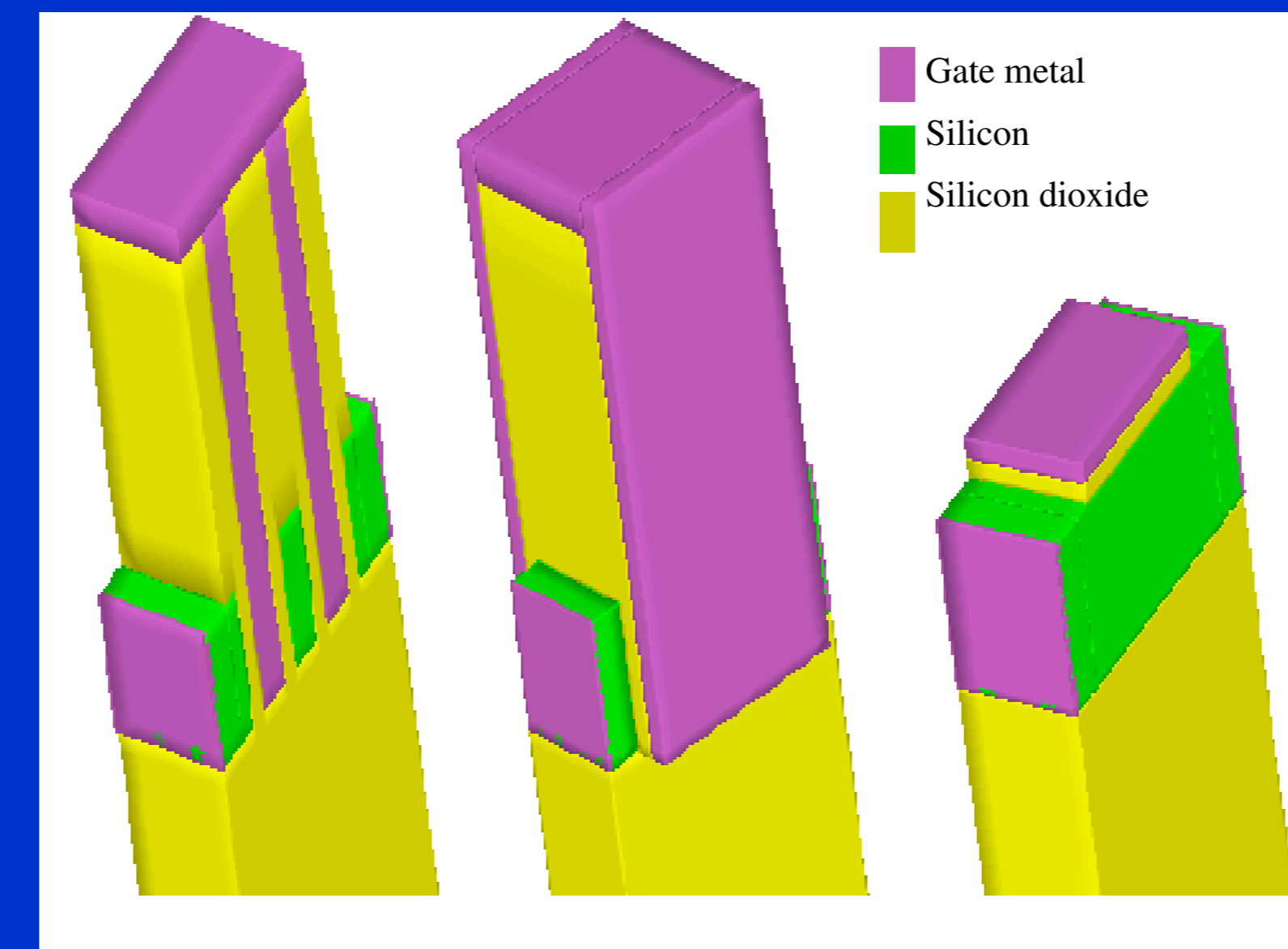
⊥-plane transport  
Small SD contact



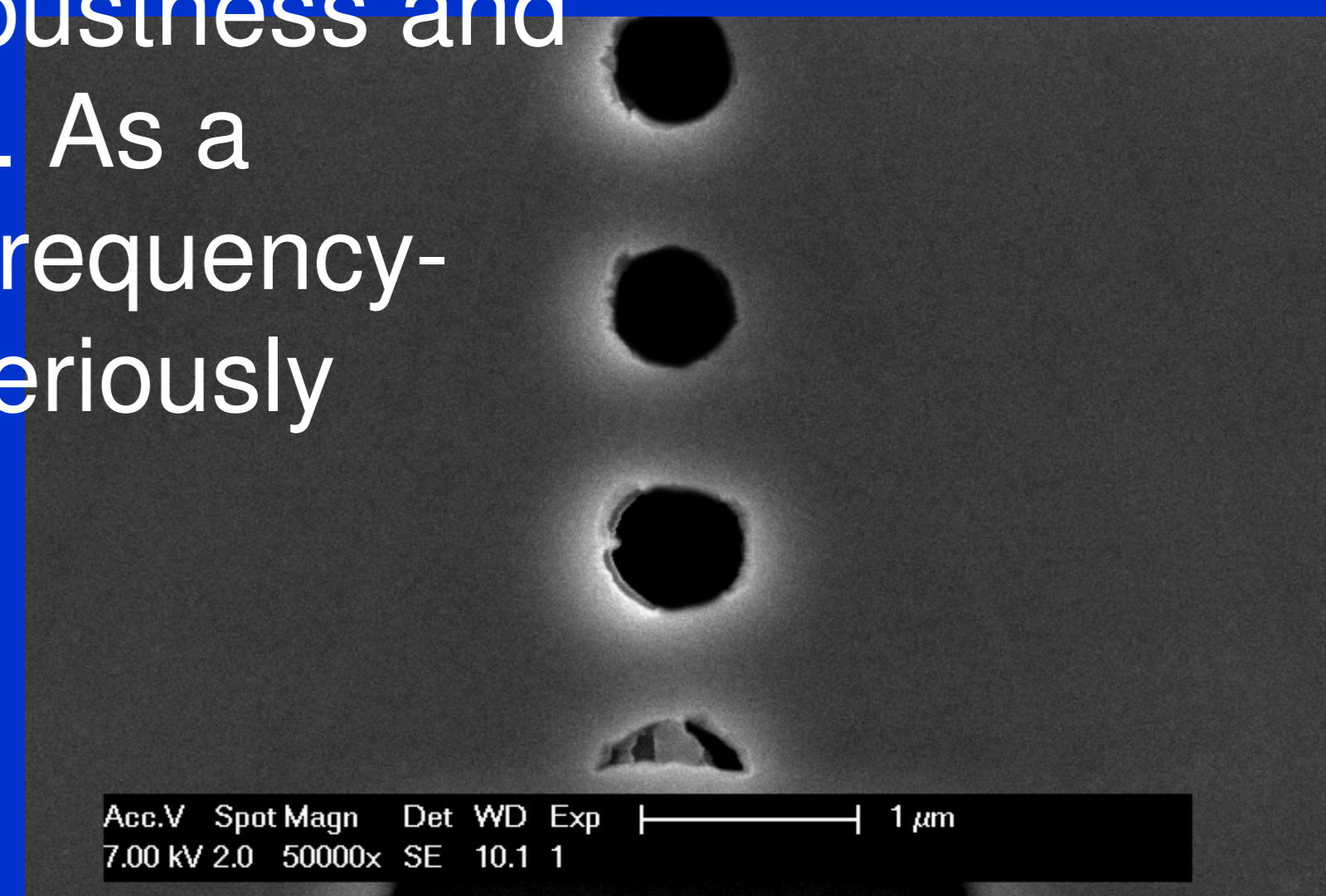
In-plane transport  
Large SD contact

## 3D TCAD performance

### Taurus (Synopsys)



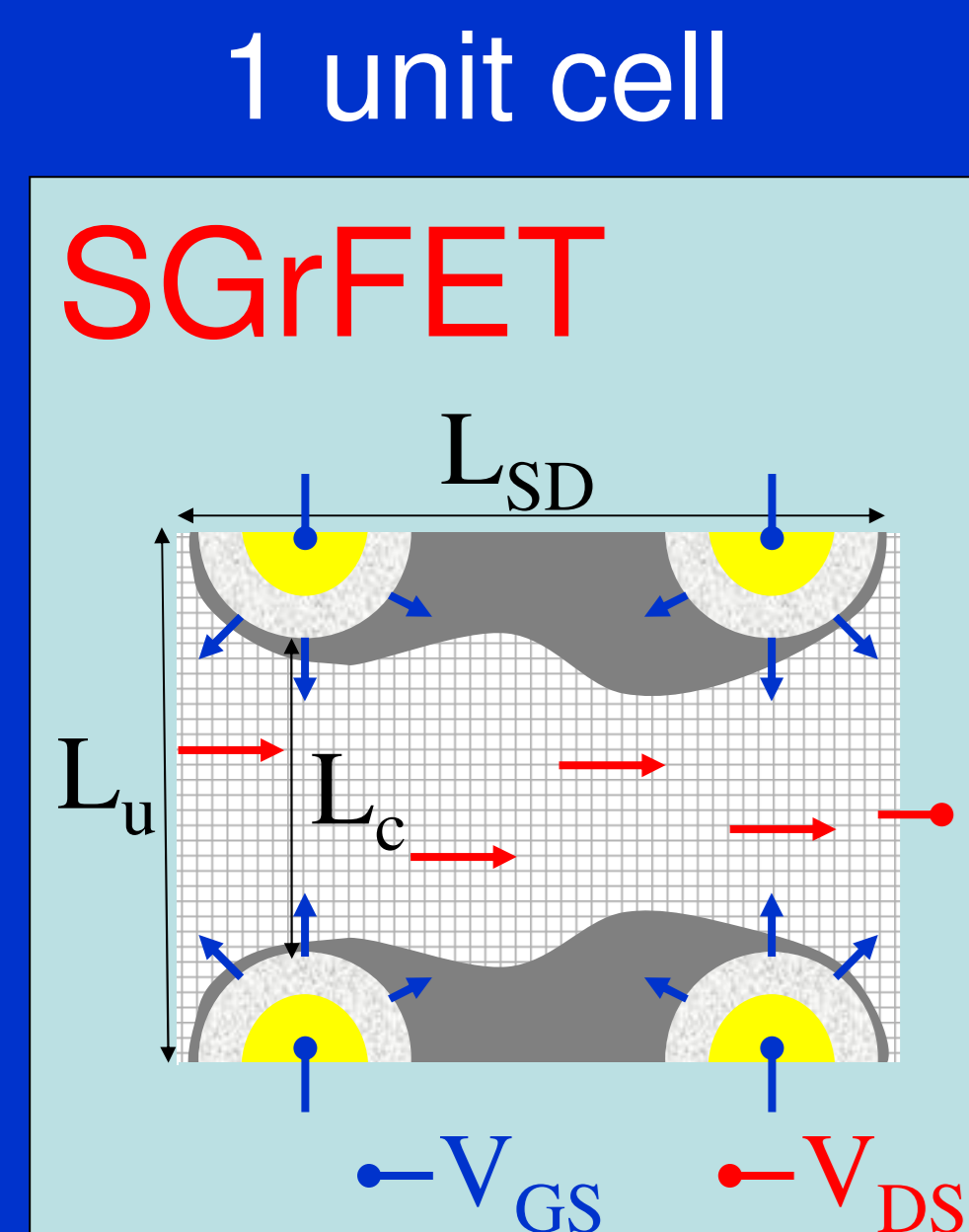
The SGrFET is a novel FET structure in SOI with a gate that is formed by cylindrical fingers perpendicular into the channel region. This FET shows excellent downscaling robustness and low power characteristics. As a consequence the cut-off frequency-voltage gain trade off is seriously relaxed in the SGrFET.



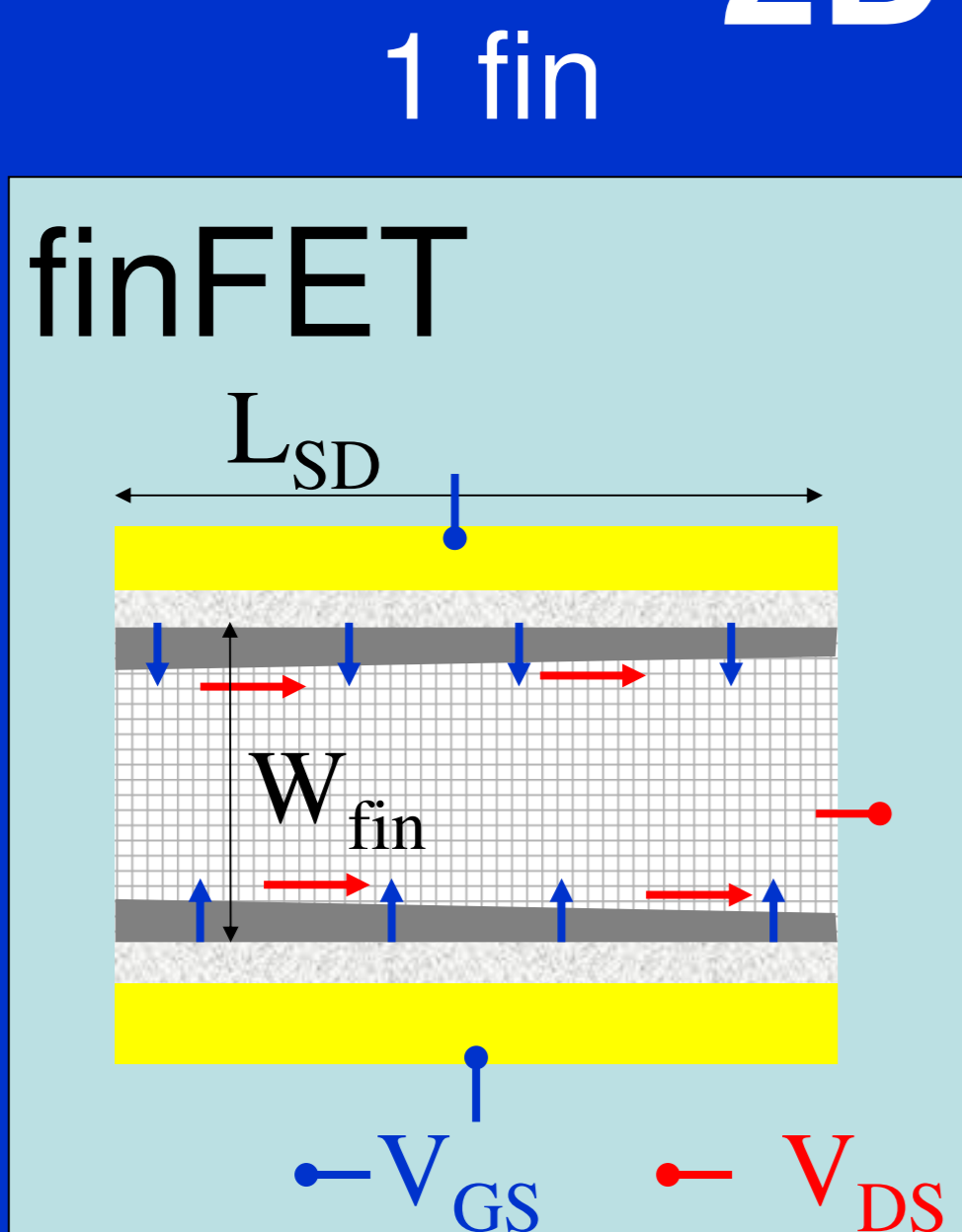
Fabrication/SEM by Mir Enterprises

## Basic transport principle/

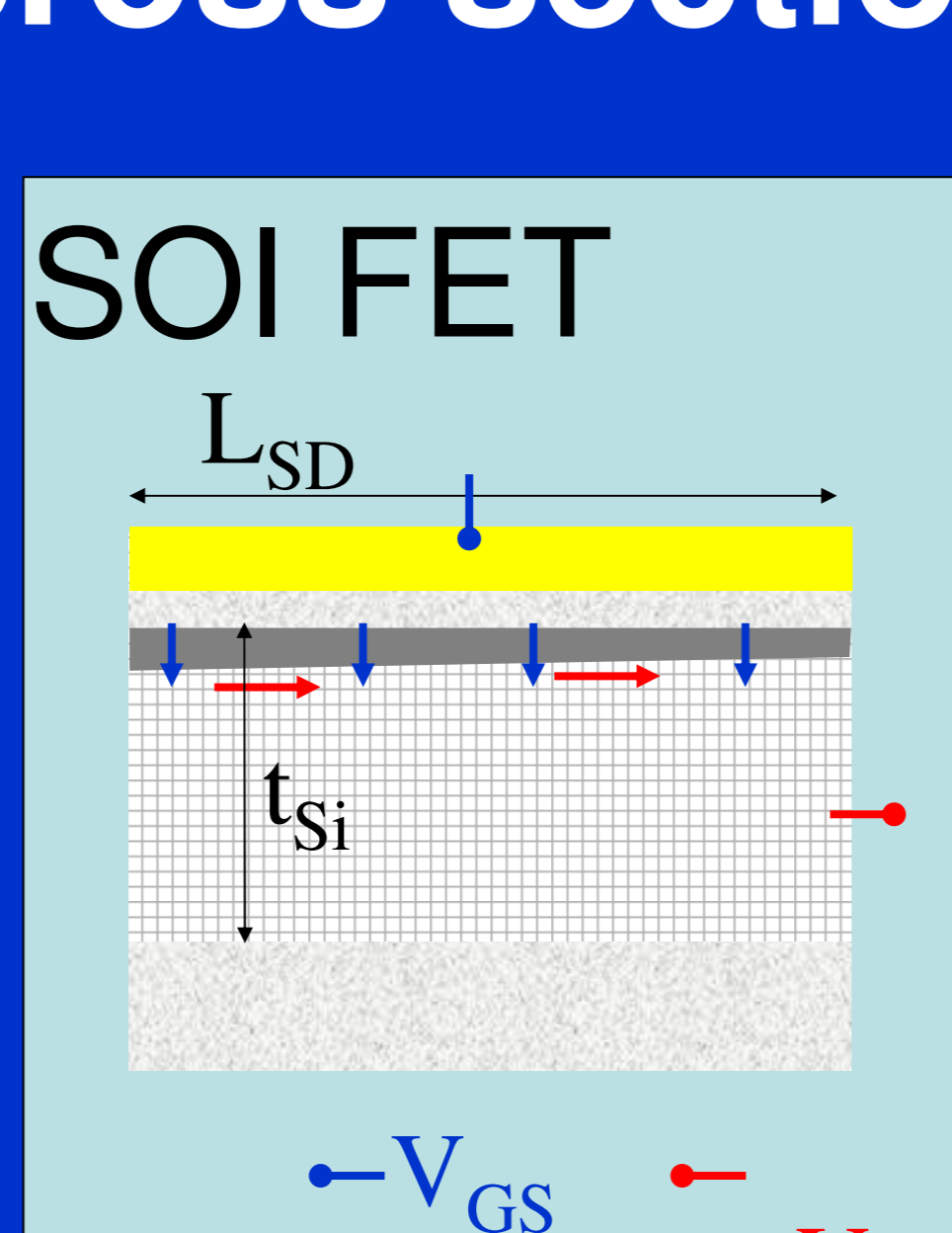
### 2D cross section



1 channel  
Depletion control  
High carrier  $\mu$   
DIBL control



2 channels  
Inversion  
Low carrier  $\mu$   
DIBL control

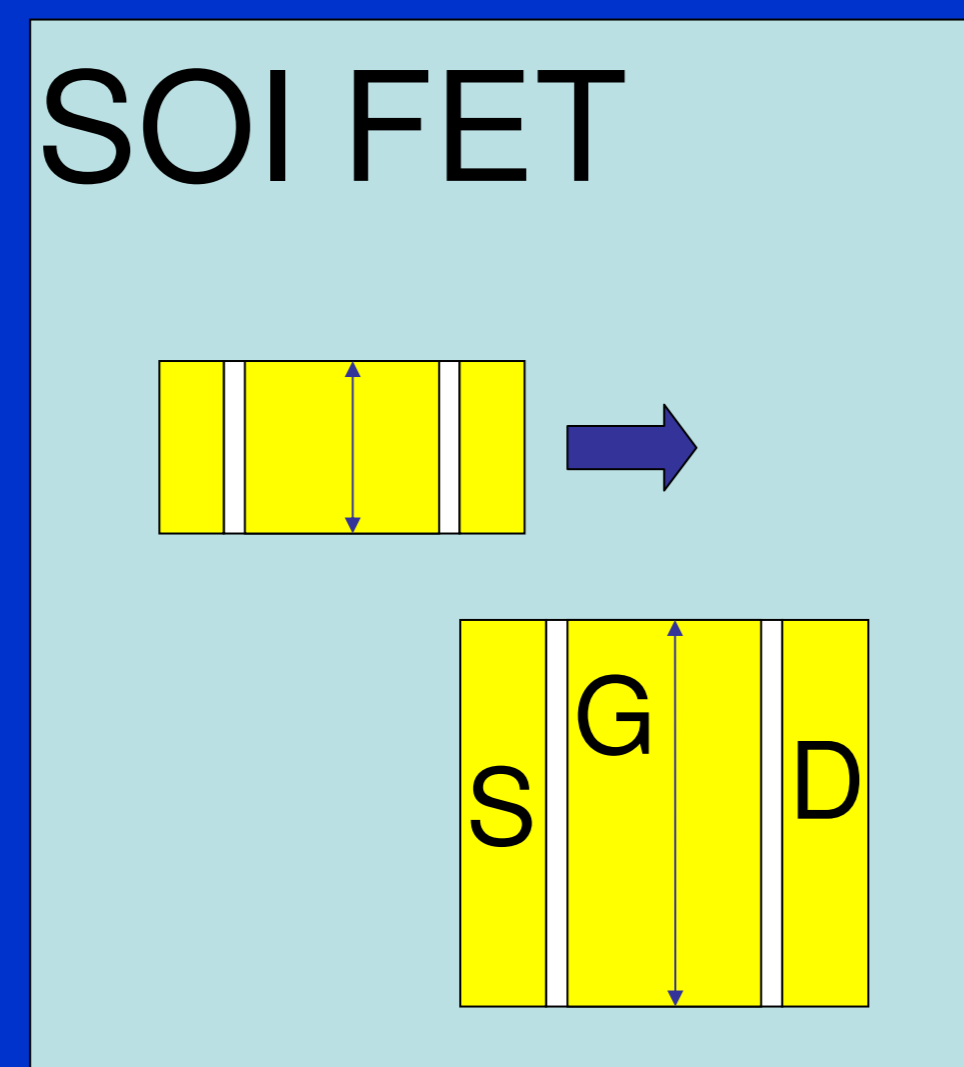
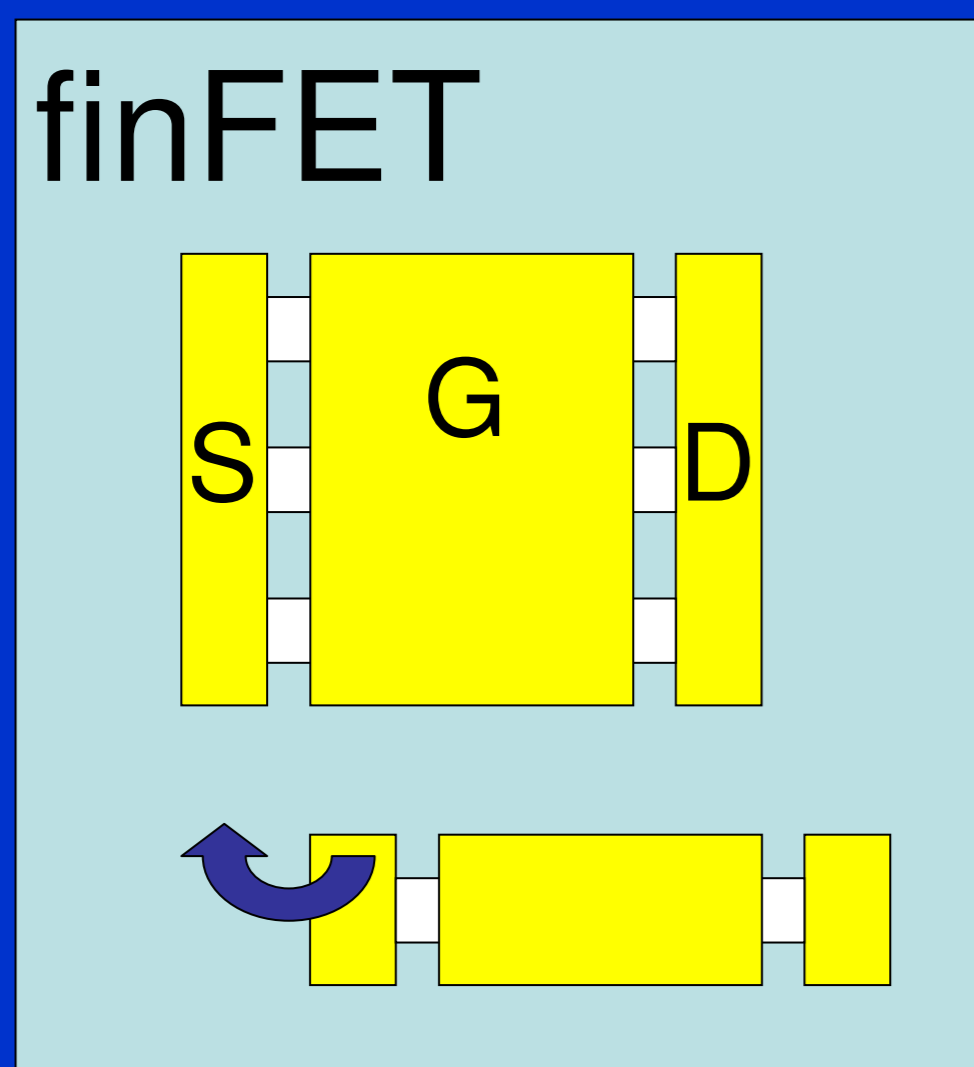
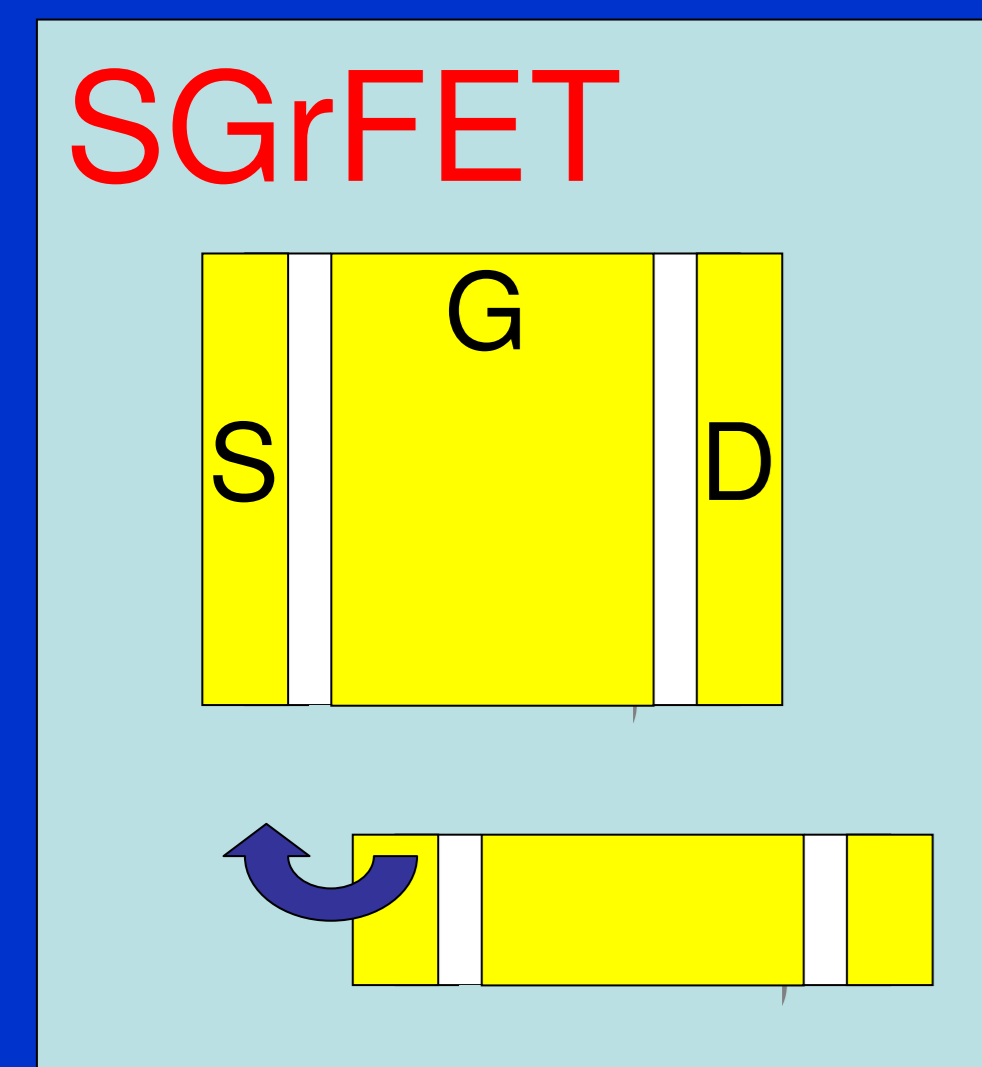


1 channel  
Inversion  
Low carrier  $\mu$

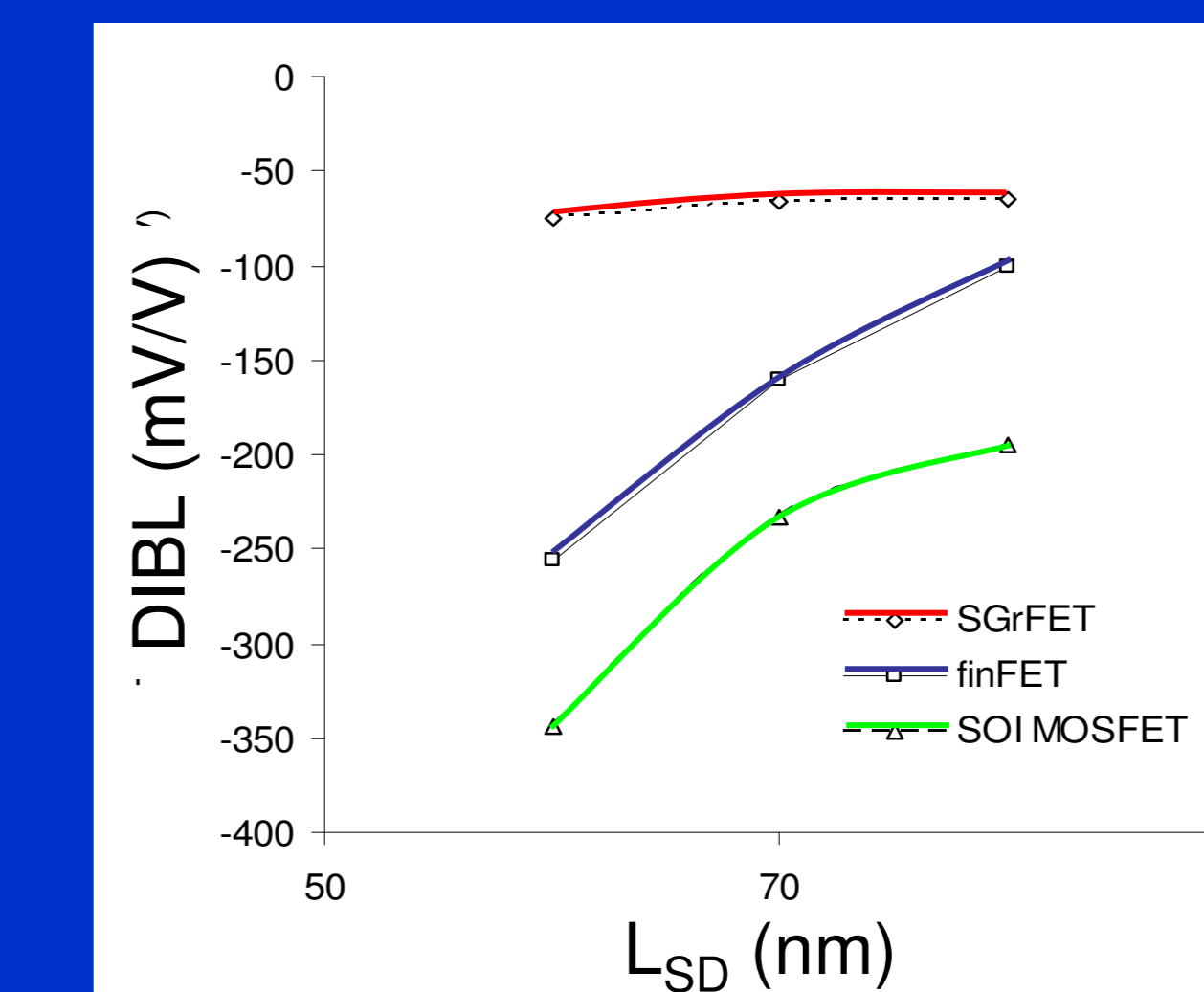
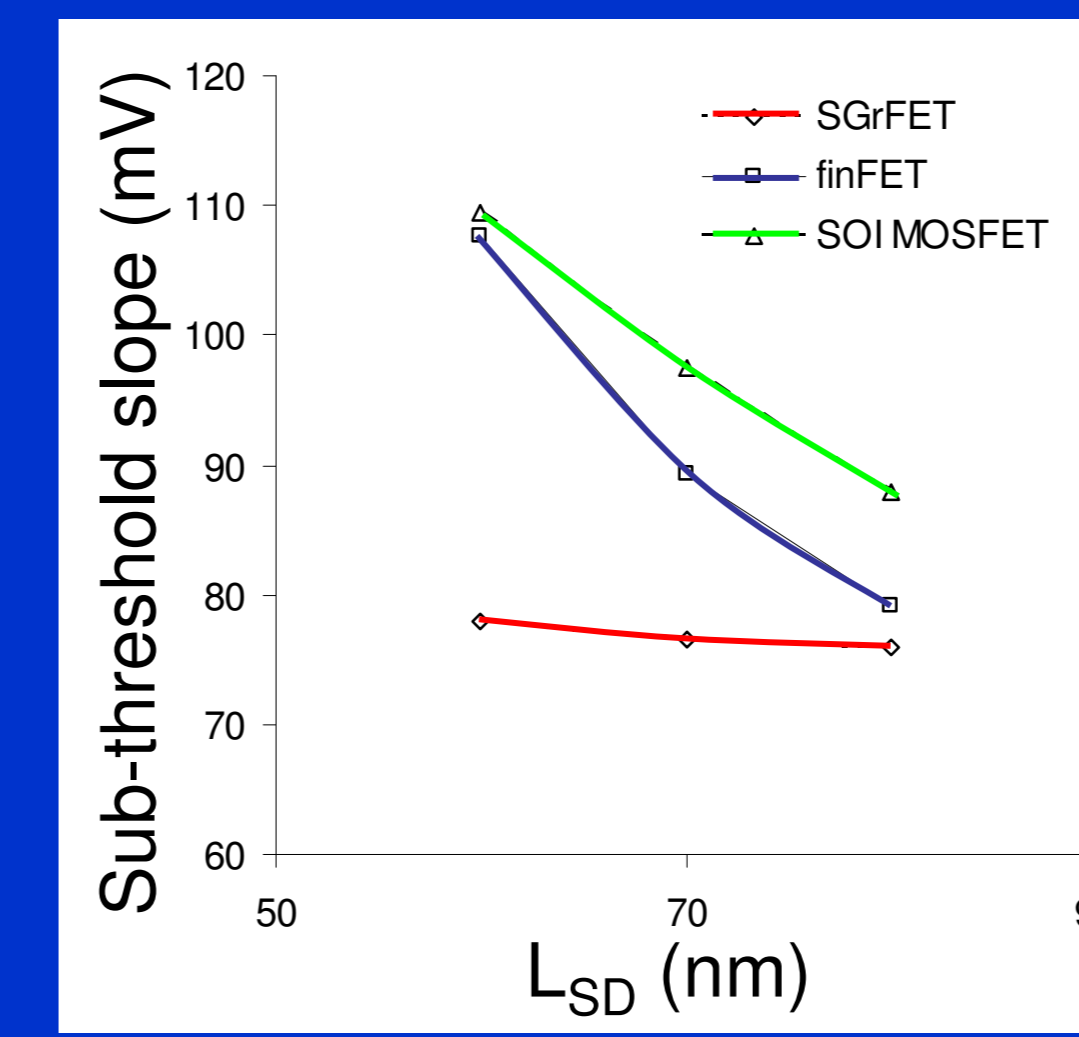
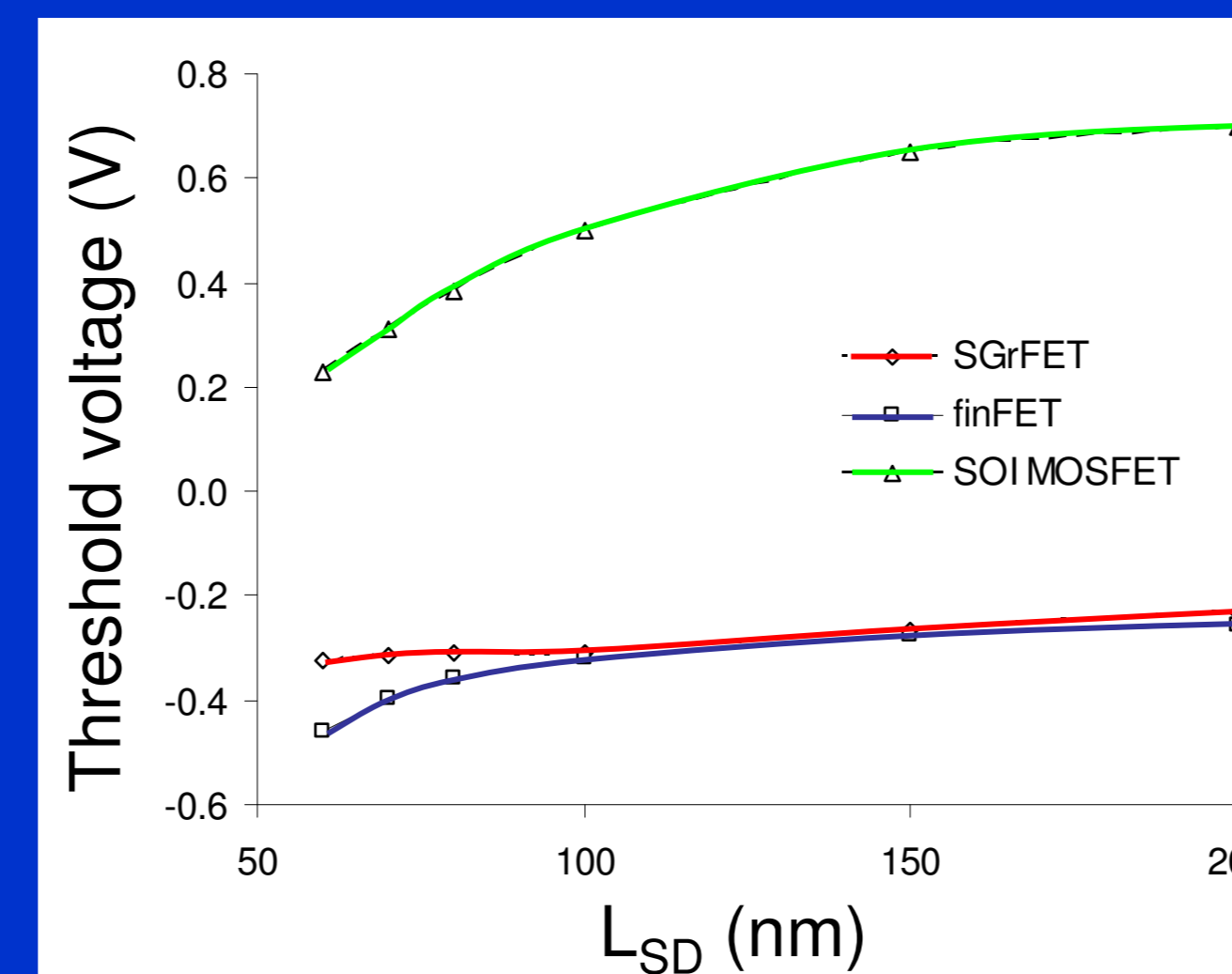
3 unit cells + 1

3 fins + 1

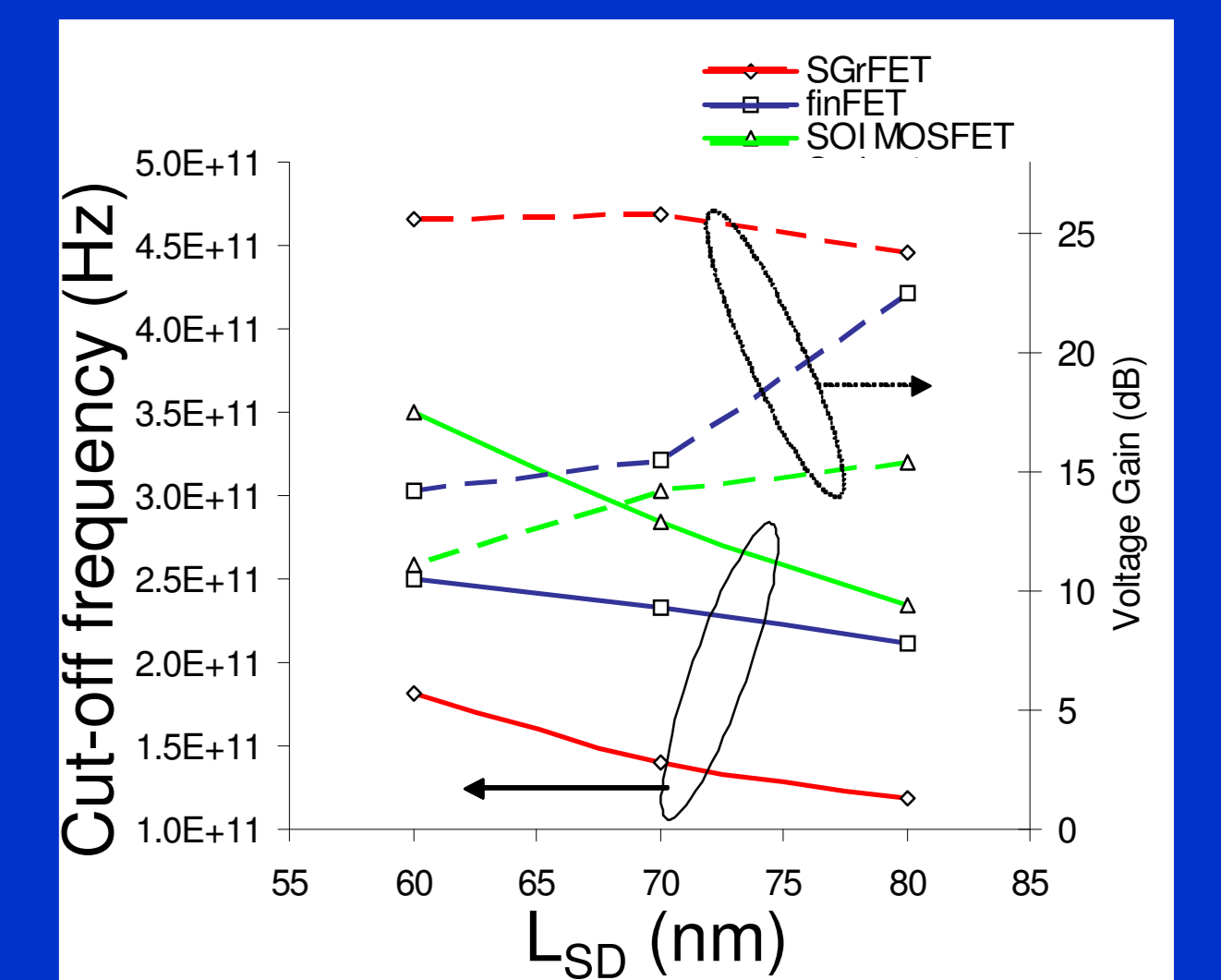
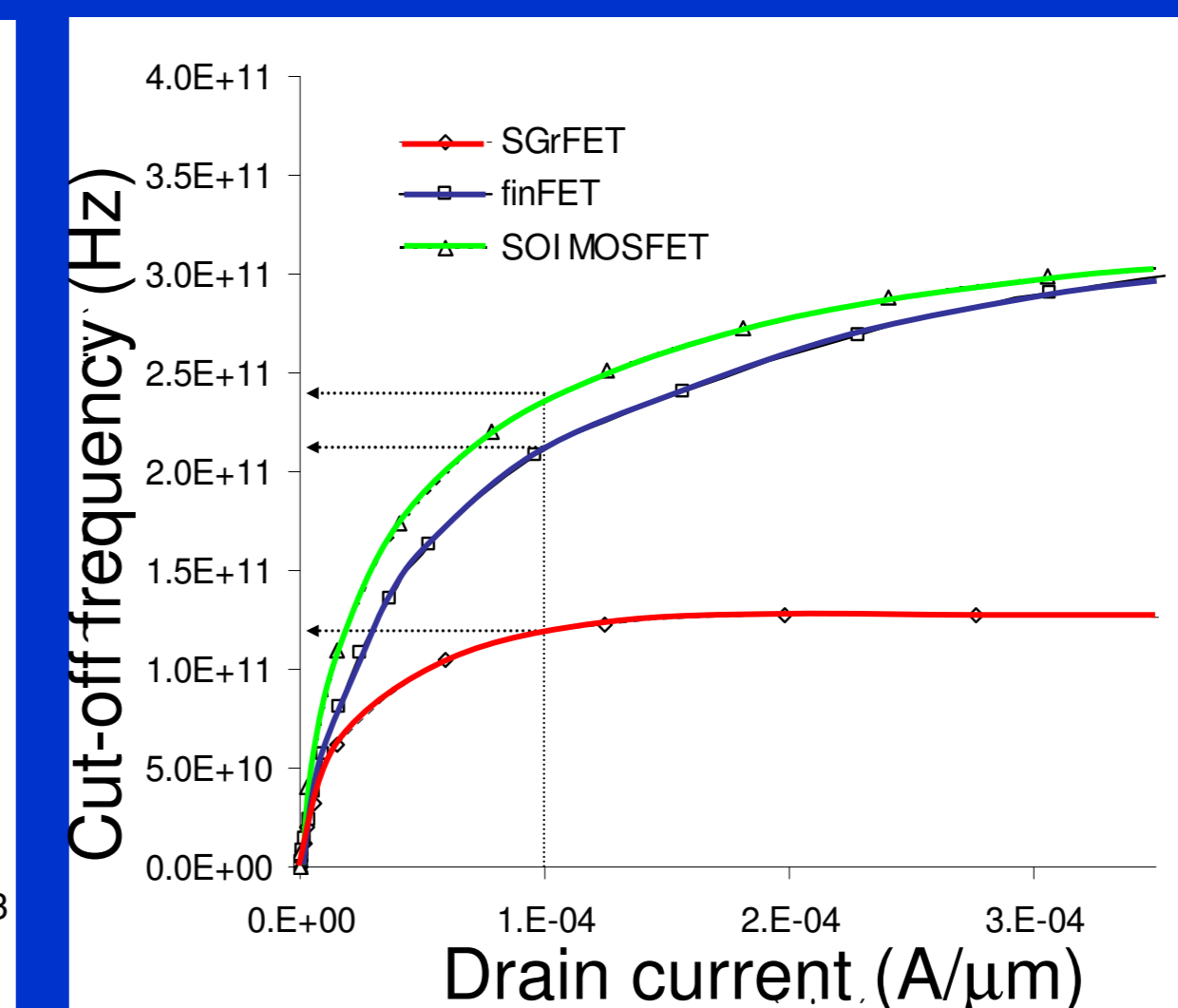
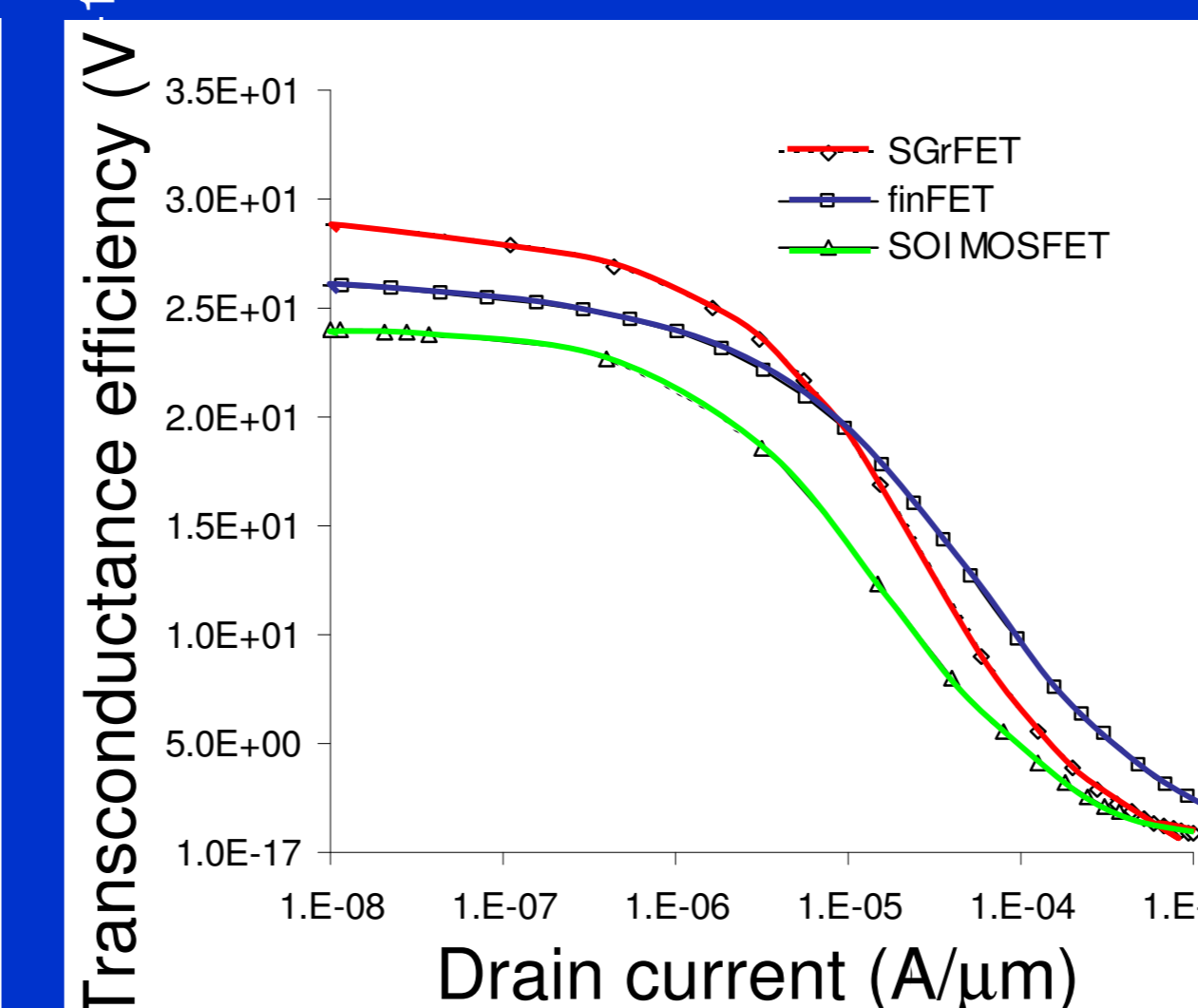
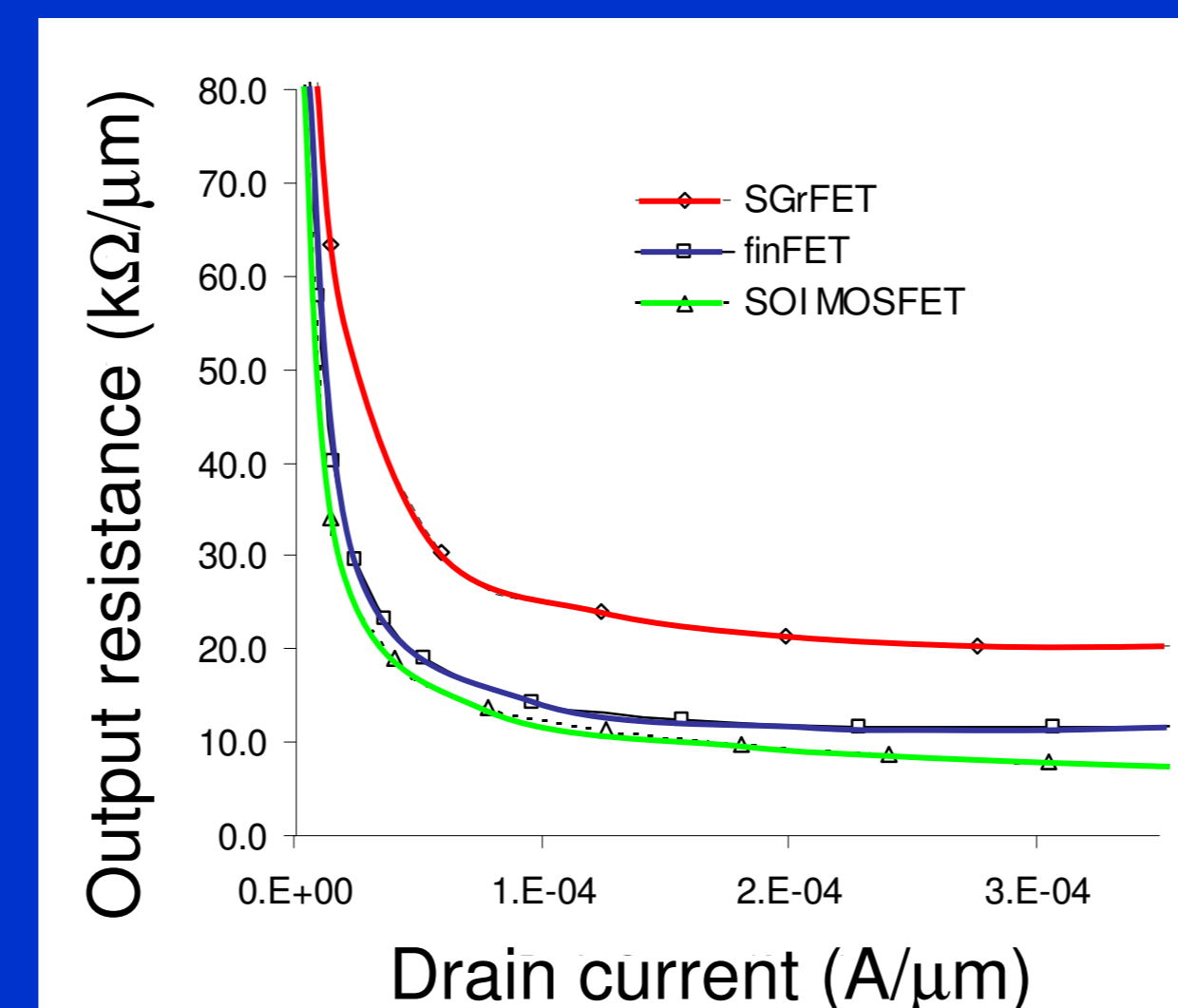
W increase



## Downscaling robustness



## RF performance



$t_{ox} = 5 \text{ nm}$   
 $L_{SD} = 80 \text{ nm}$   
 $L_U = 30 \text{ nm}$   
 $t_{Si} = 40 \text{ nm}$

	$g_m$ ( $\mu\text{S}/\mu\text{m}$ )	$g_m/I_{DS}$ ( $\text{V}^{-1}$ )	$r_o$ ( $\text{k}\Omega\cdot\mu\text{m}$ )	$g_m/g_{ds}$ (dB)	$f_T$ (GHz)
SGrFET	650	29.4	25.0	24.2	118
finFET	960	26.5	14.0	22.5	210
SOI MOSFET	470	24.0	12.0	15.4	240

Performance at  $10^{-4} \text{ A}/\mu\text{m}$   
SOI MOSFET highest  $f_T$   
SGrFET highest  $A_v = g_m/g_{ds}$